

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Ismail Kashkoush

Serial No.: 10/585,229

Filing Date: April 20, 2007

For: **SYSTEM AND METHOD FOR
SELECTIVE ETCHING OF SILICON
NITRIDE DURING SUBSTRATE
PROCESSING**

Examiner: Lan Vinh

Art Unit: 1713

Confirmation No.: 9361

Attorney Docket No.: AKR-034-US

RESPONSE/AMENDMENT

In response to the Office Action dated October 20, 2010, reconsideration is requested in view of the following amendments and remarks. This Response/Amendment is being filed within the shortened three-month statutory period of time for reply ending on January 20, 2011. No fees are believed to be due.

Amendments to the Claims begin on page 2 of this Paper.

Remarks begin on page 9 of this Paper.